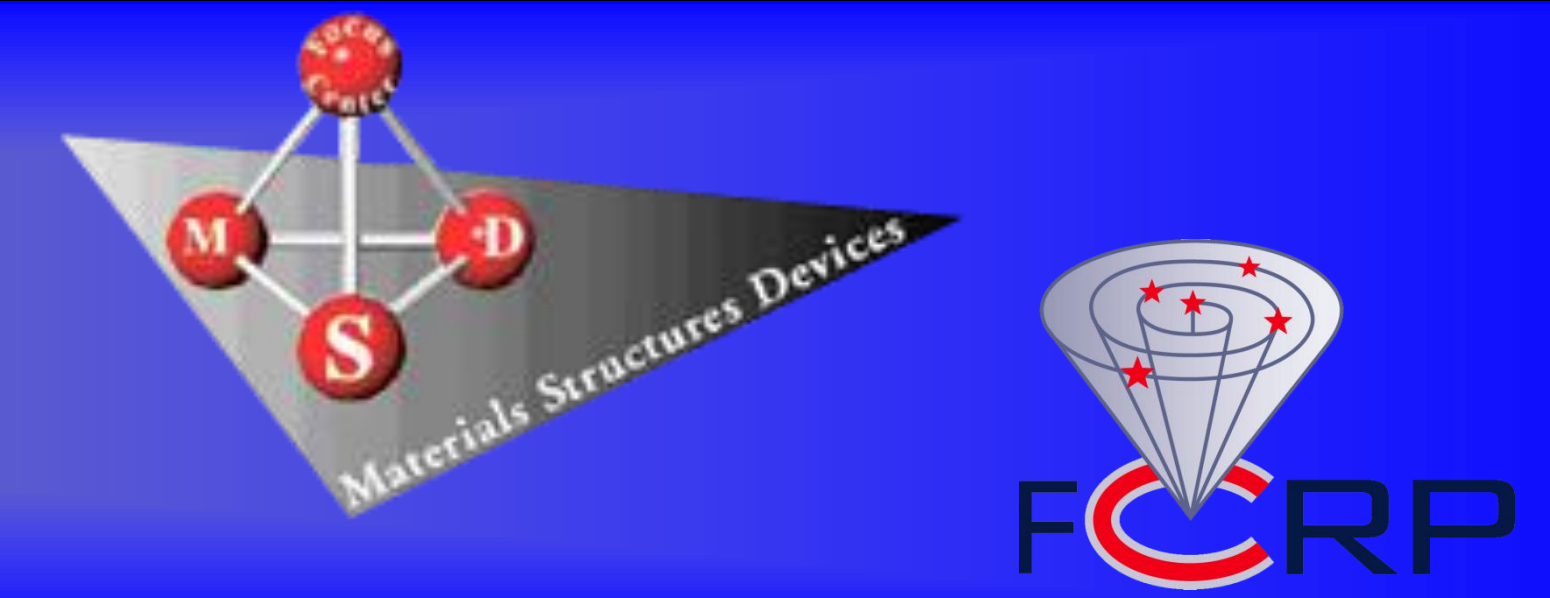


Modeling of SiGe material for ultra-scaled CMOS device applications



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Why SiGe material ?

MOTIVATION

Higher drive current and shrinking device dimensions : **Moore's Law**

Bulk Mobility (cm ² /Vs)[1]	Si	Ge
Electrons	1400	3900
Holes	450	1900

New channel material for higher current

3D nanostructure devices for better electrostatics.

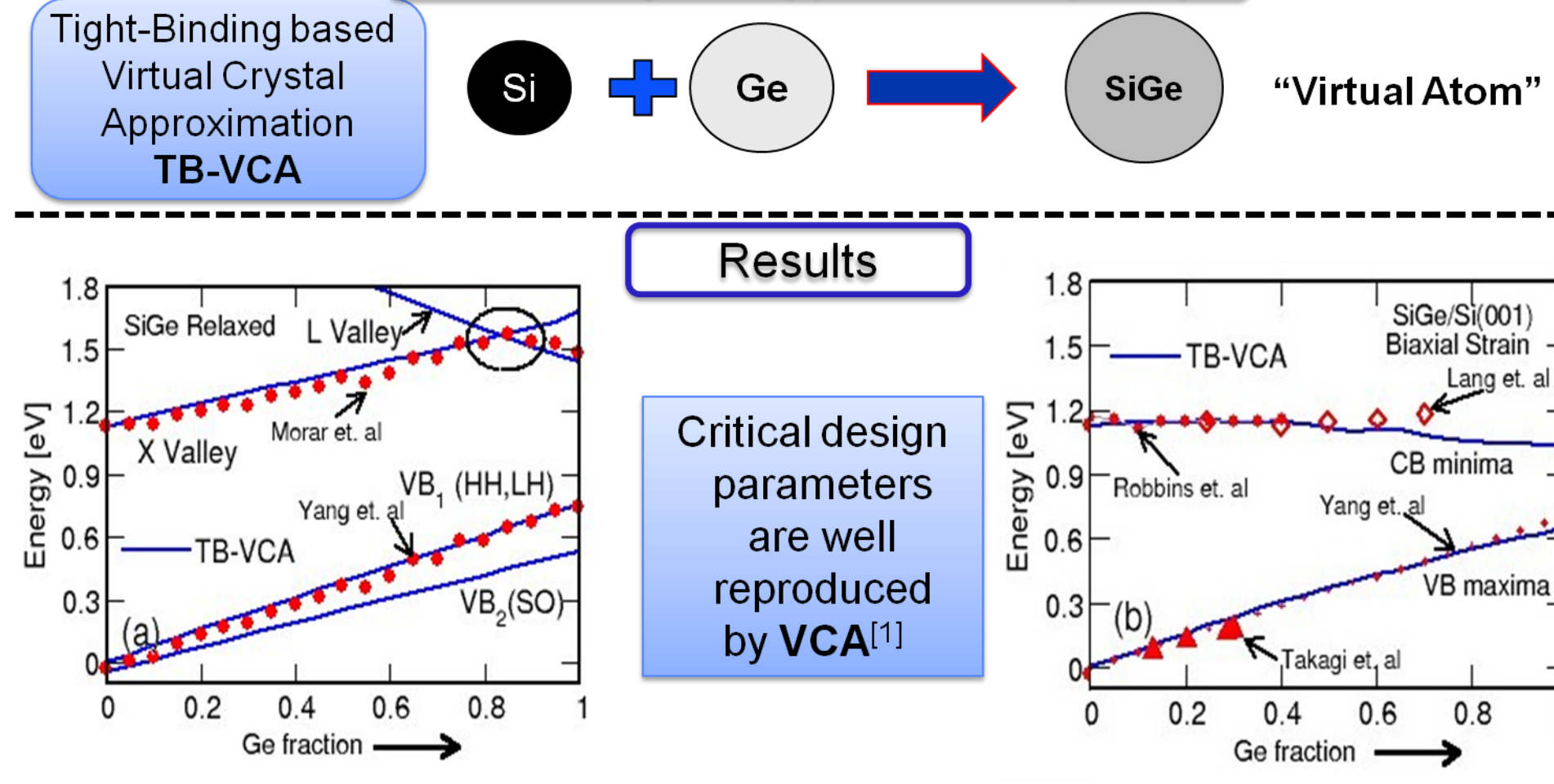
OBJECTIVE

- Development of Electronic Structure model for SiGe
 - Virtual Crystal Approximation (VCA)
 - Random Alloy Treatment (RAT)
- Understand alloy disorder in SiGe for transport.
- Extract mobility information using Green's Function approach.

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Electronic Structure : VCA method

Virtual Crystal Approximation(VCA)

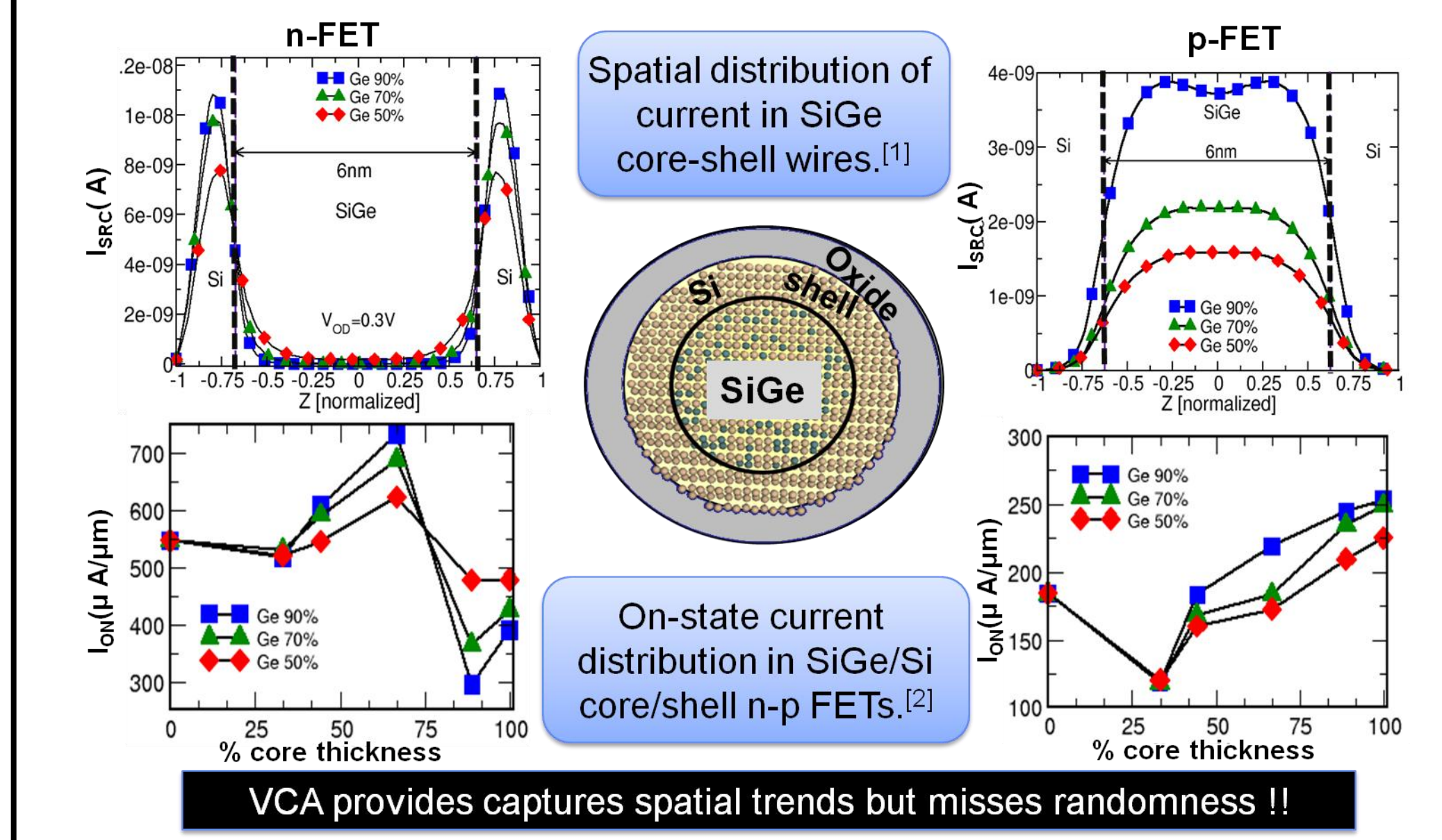


Bulk SiGe electronic properties captured well by TB-VCA.

[1] A. Paul, S. Mehrotra, M. Luisier and G. Klimeck, IEEE EDL, April, 2010

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Transport in Core/Shell SiGe/Si - TB VCA



[1] A. Paul et al. ISPRS, Dec. 2009.
[2] A. Paul et al. IEEE EDL, April, 2010

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Random Alloy Treatment (RAT)

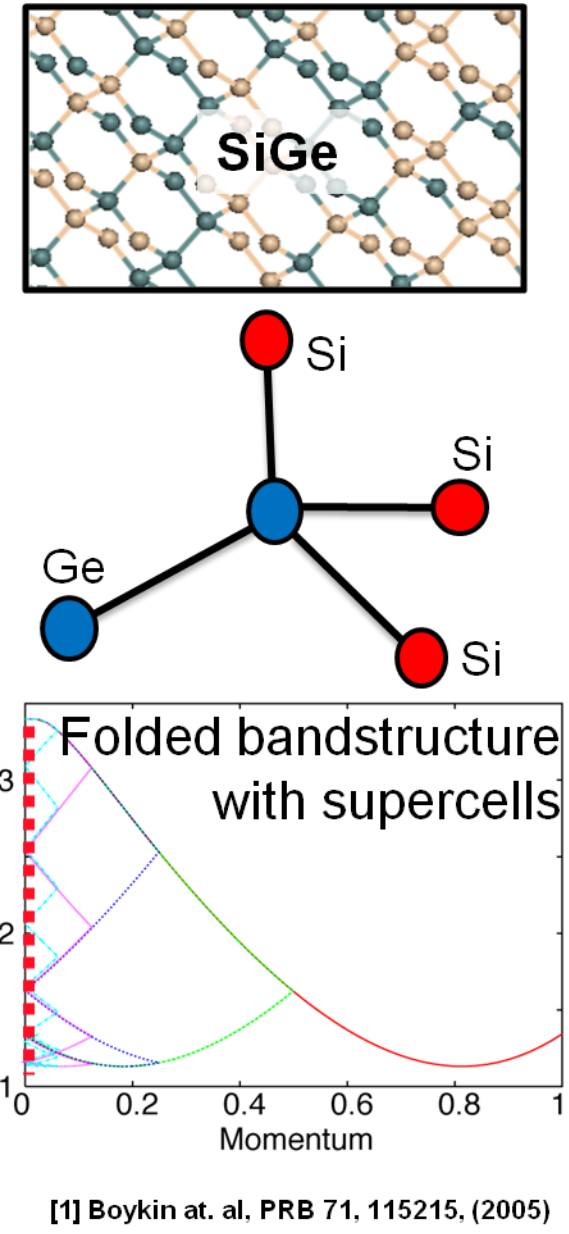
- SiGe - alloy with inherent disorder.
- No periodicity or concept of 'E(k)'.
- Treat Si and Ge atoms separately.

Relax SiGe structure using VFF Keating model.

Pauling limit: Bonds maintain distinct bulk value.
Vegard limit: All bonds linearly averaged.

Electronic structure using zone-unfolding[1].

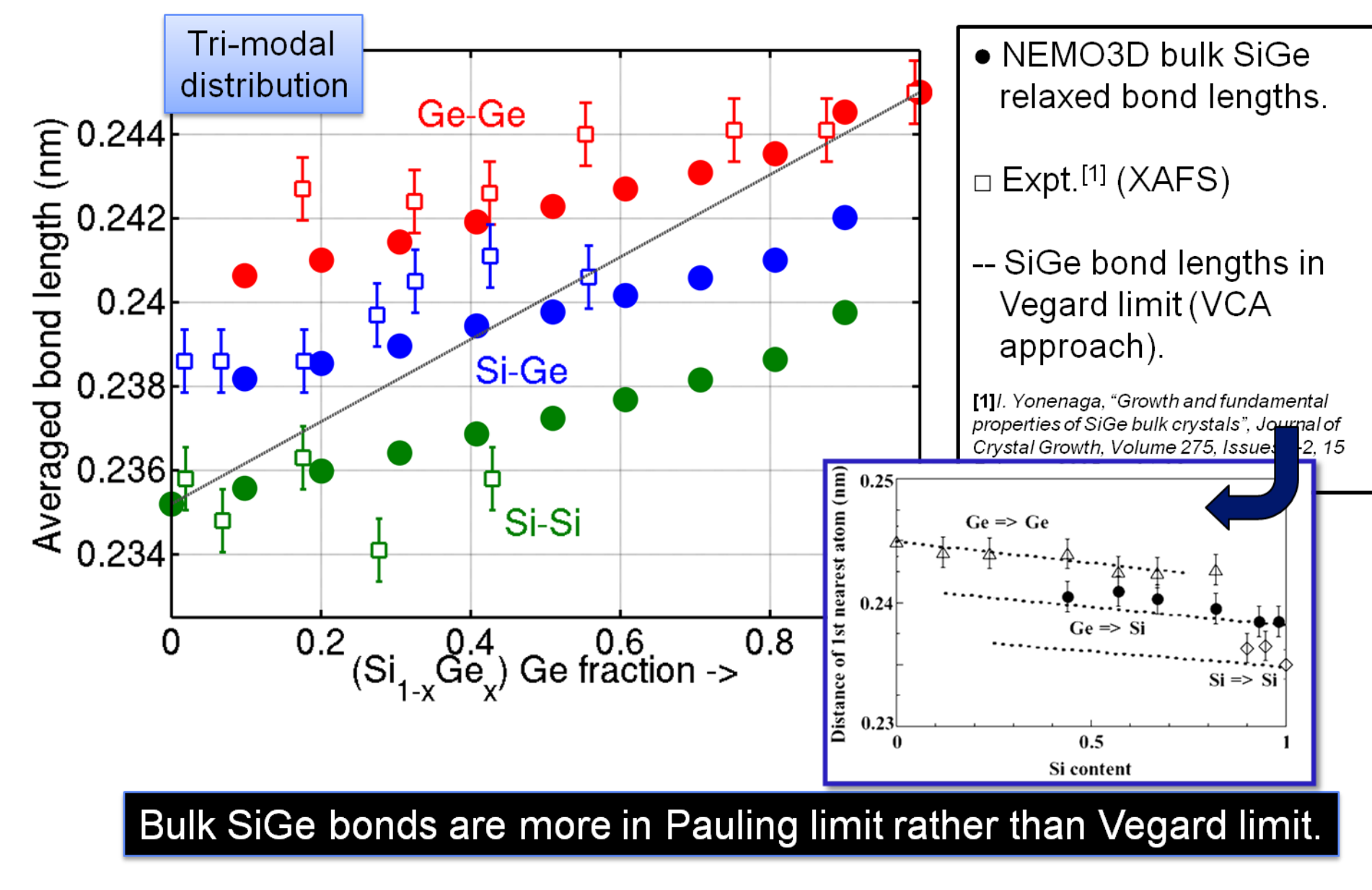
Supercell calculations to determine bandedges in a disordered system.



[1] Boykin et al. PRB 71, 115215, (2005)

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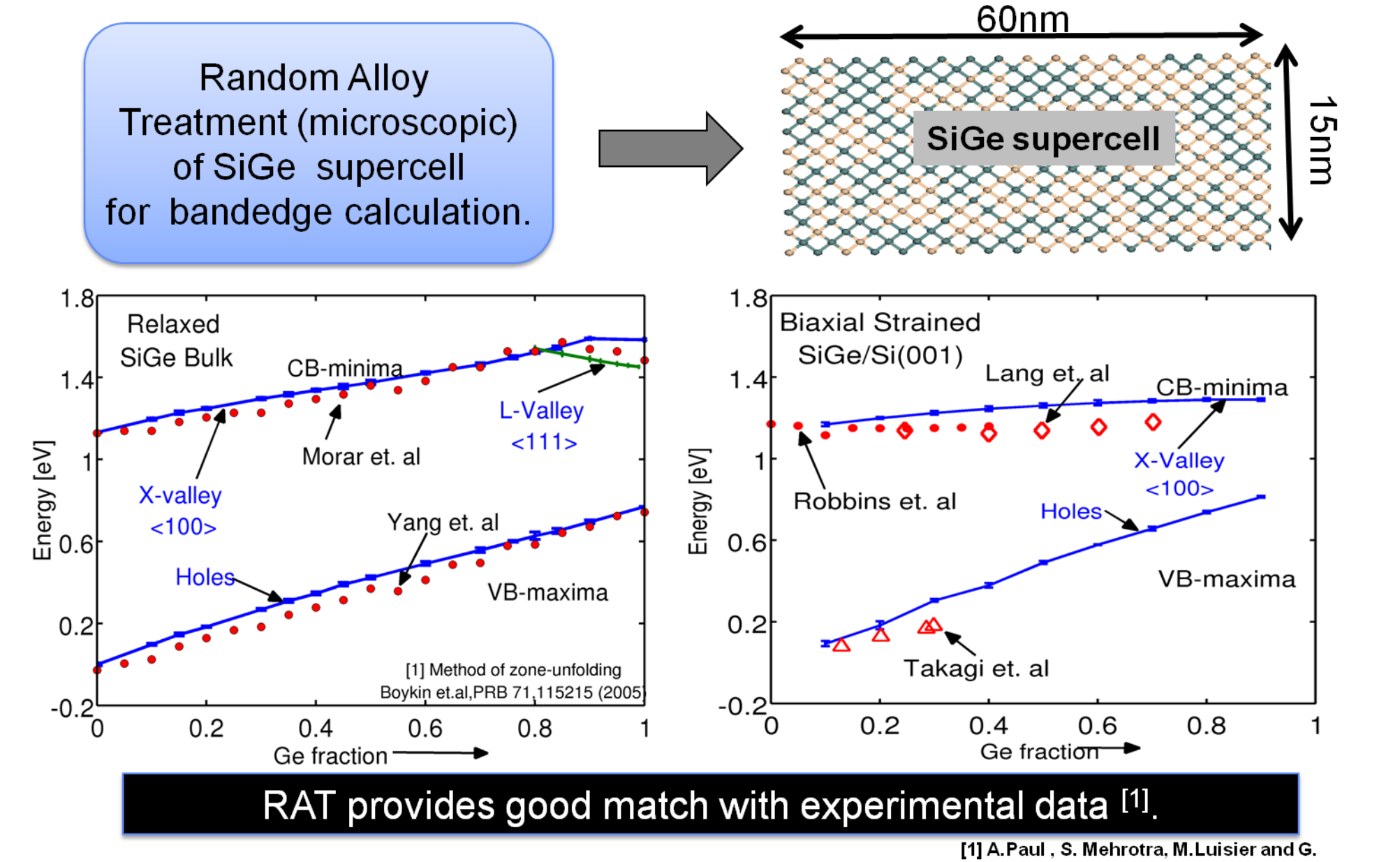
SiGe bond length benchmarking



Bulk SiGe bonds are more in Pauling limit rather than Vegard limit.

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Bulk SiGe bandedges using supercell



[1] A. Paul, S. Mehrotra, M. Luisier and G. Klimeck, IEEE EDL, April, 2010

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Alloy Scattering

CLASSICAL APPROACH

$$\mu_A = \frac{\sqrt{2\pi e^2 N_0}}{3x(1-x)m^{*5/2}} \frac{1}{(\Delta E)^2 KT}$$

Brook's formula[1] for alloy scattering.

Alloy Scattering with a fitting parameter $\rightarrow \Delta E$

ΔE fitted for bulk only, can change in nanostructures!

MICROSCOPIC TREATMENT

RANDOM ALLOY APPROACH

Alloy scattering potentials embedded in atomistic representation!

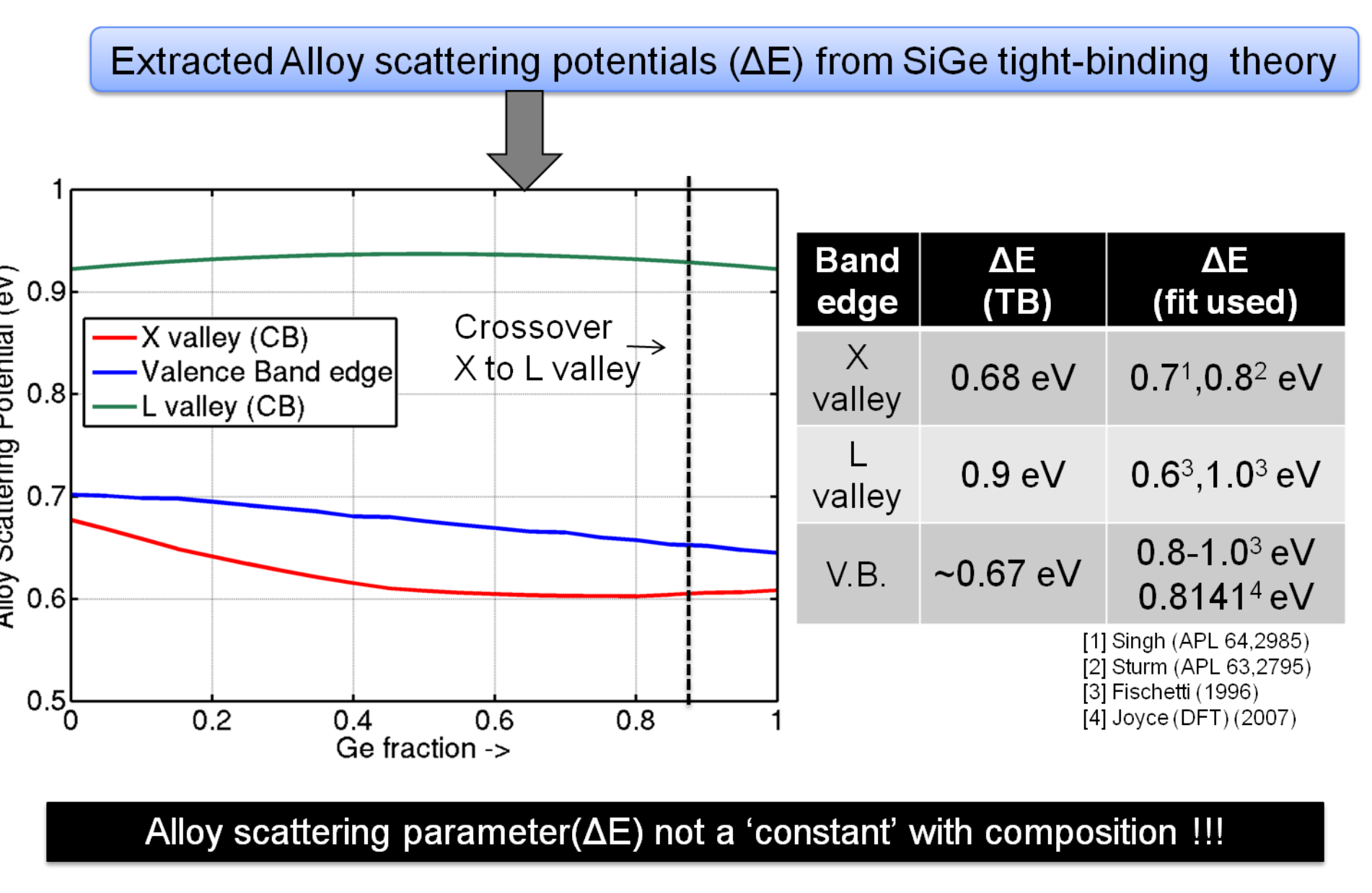
$$\Delta E^2 = \frac{N_{atom}}{x(1-x)} \langle \phi(k_f) | H_{RAT} - H_{VCA} | \phi(k_i) \rangle^2$$

Random alloy provides a direct approach to treat alloy scattering.

[1] S. Krishnamurthy, et al. APL 47, 160, (1985).

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Alloy Scattering Potentials from RAT



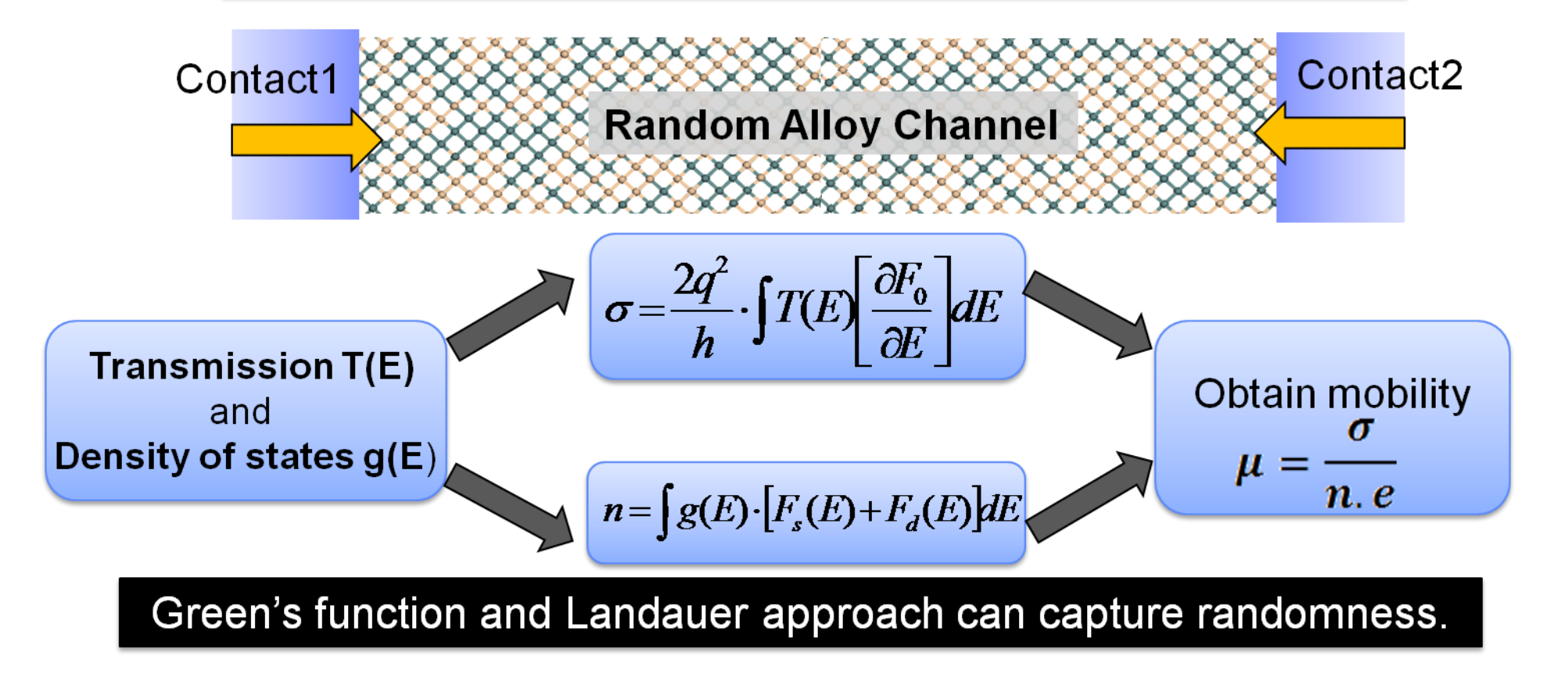
Alloy scattering parameter(ΔE) not a 'constant' with composition !!!

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Transport in Alloy: Green's Function

How to capture randomness in disordered system ?

Transmission T(E) calculation using Green's function provides a good way to capture disorder.

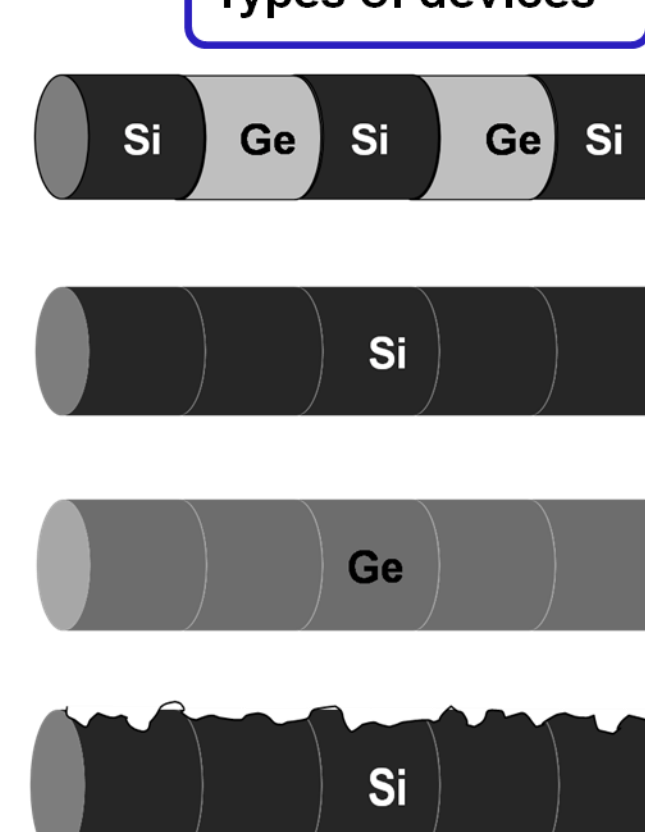


Green's function and Landauer approach can capture randomness.

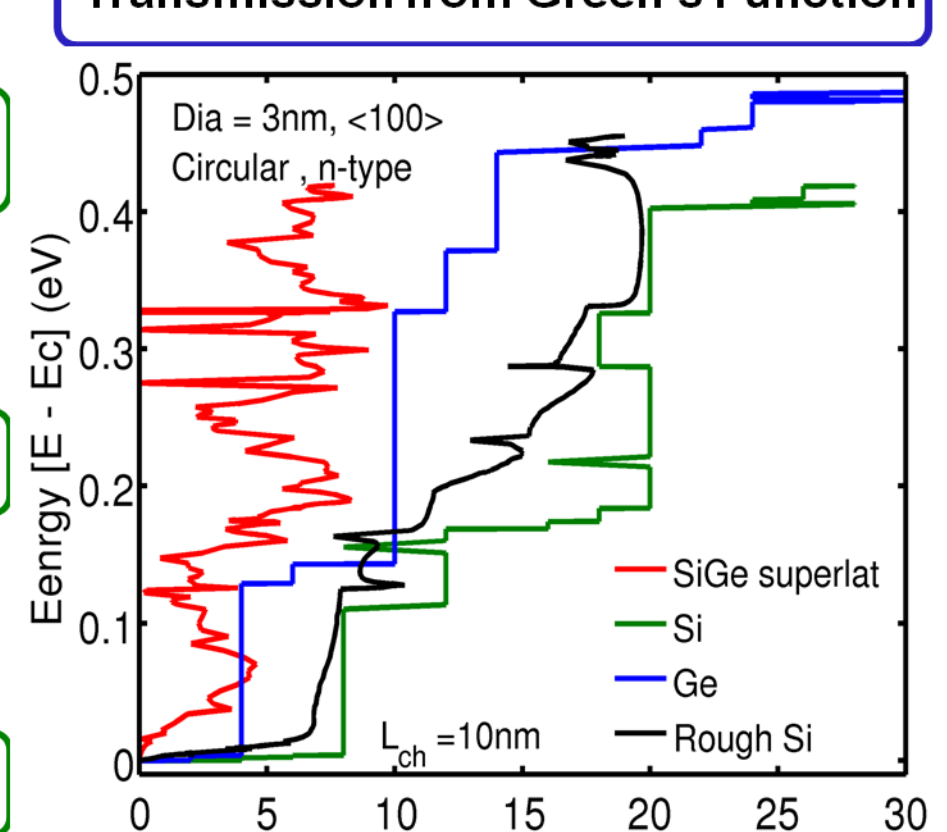
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Comparison of Transmission

Types of devices



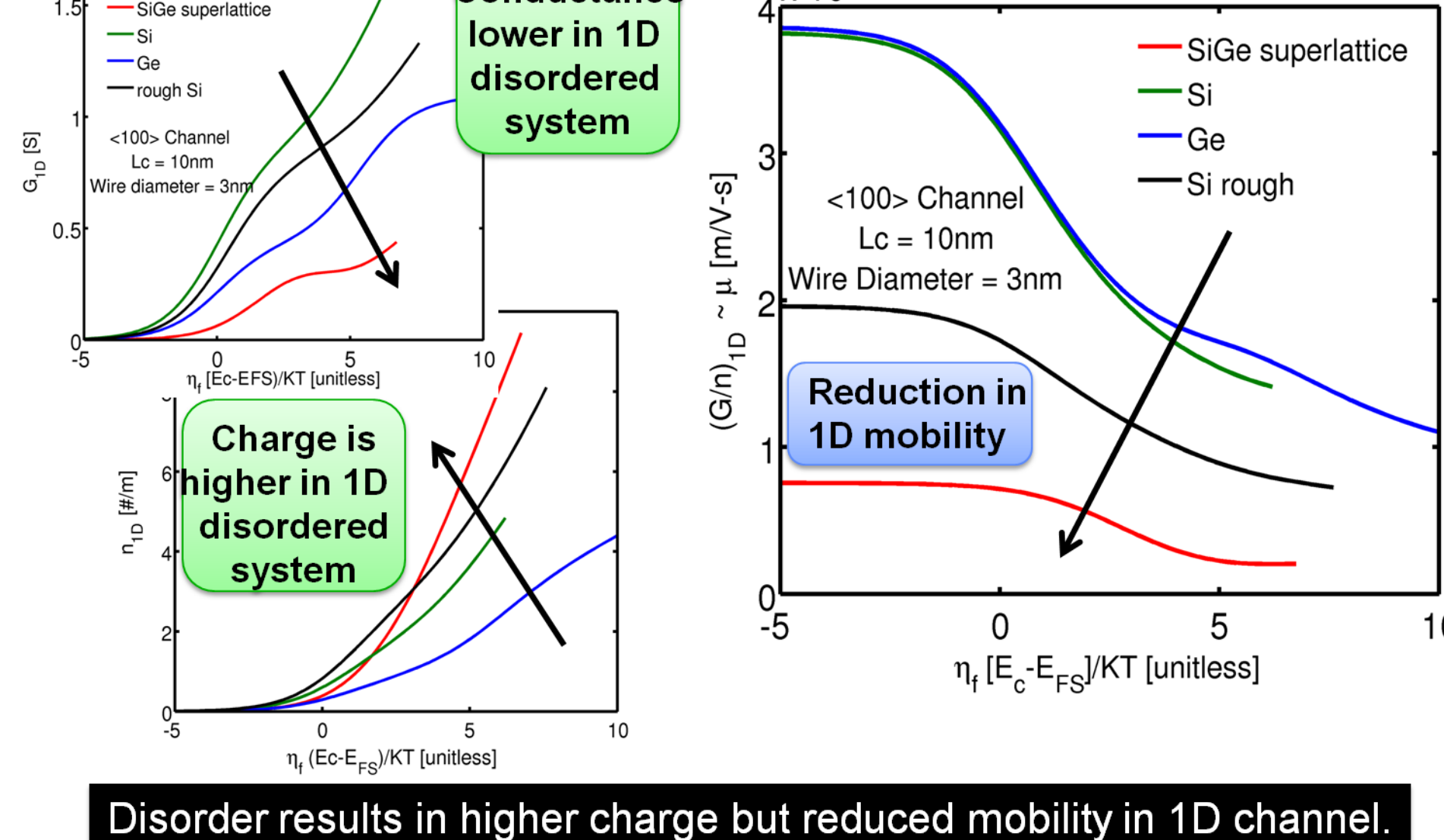
Transmission from Green's Function



Green's function method can model disorder in the channel.

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Transmission to terminal characteristics



Disorder results in higher charge but reduced mobility in 1D channel.

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Conclusion and Future Work

IMPLEMENTED METHODS

- Virtual Crystal Approximation (VCA) homogenizes material treats disorder as a perturbation.
- Random Alloy Treatment represents disorder explicitly.
- Transport in disordered channel using Green's function.

IMPACT

- Experimental data benchmarked. Perform transport in ballistic limit.
- Bond lengths and bulk alloy SiGe bandedges benchmarked.
- Benchmarked experimental alloy scattering potential(ΔE) parameter.
- Mobility computed from transmission in disordered system.

FUTURE WORK

- Calibration of Si-Ge electronic structure (tight binding parameters)
- Understand quantum transport in nano-structured SiGe channel devices.
- Transport simulation of Ultra Thin Body and Nanowire SiGe devices.

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